

# FAX RECEIVED

APR 2 6 2003

**TECHNOLOGY CENTER 2800** 

465-758P

### IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant:

Jun S. LEE

Conf.:

5244

Serial No.:

09/722,583

Art Unit:

2823

Filed:

November 28, 2000

Examiner: B. Kebede

For:

METHOD FOR FABRICATING CAPACITOR OF

SEMICONDUCTOR DEVICE

## SUPPLEMENTAL AMENDMENT UNDER 37 C.F.R. §1.111

**Assistant Commissioner for Patents** Washington, DC 20231

February 5, 2003

Sir:

In response to the Office Action mailed November 7, 2002 (Paper No. 14), the following amendments and remarks are respectfully submitted in connection with the above-identified application:

#### IN THE CLAIMS:

#### Please rewrite claims 1 and 4 as follows:

1. (Twice Amended) A method for fabricating a capacitor of a semiconductor device comprising:

depositing a nitride film and an oxide film over a substrate, the oxide film being deposited on the nitride film by chemical vapor deposition;

sequentially etching the oxide film and the nitride film using a patterned photoresist as a mask;